

Fabrication of high performance thin films from metal fluorocomplex aqueous solution by the liquid phase deposition

Hnin Yu Yu Ko^a, Minoru Mizuhata^b, Akihiko Kajinami^b, Shigehito Deki^{b,*}

^aDepartment of Chemistry, School of Science and Technology, Kwansai Gakuin University, 2-1 Gakuen, Sanda, Hyogo 669-1337, Japan

^bDepartment of Chemical Science and Engineering, Faculty of Engineering, Graduate School of Science and Technology, Kobe University, Rokkodai, Nada, Kobe 657-8501, Japan

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Abstract

The hetro-structured oxide thin films from metal fluorocomplex solution have been prepared by the liquid phase deposition (LPD) method. The Pt/Nb₂O₅ and Au/Nb₂O₅ composite films can be prepared from a mixed solution of niobium source, H₃BO₃, Pt(NH₃)₄Cl₂ and HAuCl₄ aqueous solutions under the ambient temperature and atmosphere. In the case of Au/SiO₂ composite film, (NH₄)₂SiF₆ solution is used as a mother solution. The Pt and Au ionic species are deposited in Nb₂O₅ and SiO₂ matrices. They are reduced to their metallic state after treatment above 200 °C. The size of dispersed particles can be controlled by heat treatment temperature. It is also clear that, gold nanoparticles are also found to interact with SiO₂, although the interaction is smaller than that with Nb₂O₅ showing the size of Au nanoparticles remain smaller in Nb₂O₅ than in SiO₂.

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Keywords: Synthesis; Nanoparticles; Liquid phase deposition; Metal oxide; Thin film; Hetro-structure

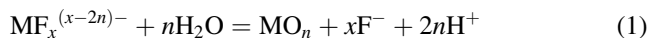
1. Introduction

Nano-sized noble metal particles, because of their surface and quantum-size effects, display many novel properties, such as high catalytic activities, non-linear optical properties, and various properties from a fundamental viewpoint. In the materials for the production of non-linear optical devices, it is important to ensure a layer or circuit pattern. The use in a practical application, however, imposes on these materials quite severe restrictions concerning accurate control of the particles: distribution, shape, dimensions and homogeneity.

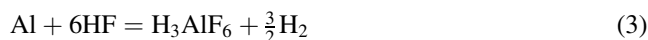
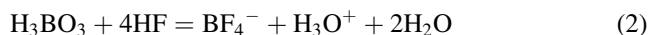
Accordingly, considerable effort has been focused on the development of synthetic techniques. Actually, the composite films have been fabricated using various methods, such as rf sputtering, ion-implantation, and sol-gel method [1–3]. The liquid phase deposition (LPD, also known as chemical bath deposition) method which has been developed and reported previously is a wet process employed to prepare metal oxide thin films from aqueous solutions as low temperatures (30–50 °C) [4,5]. Compared to vapor deposition techniques, the LPD method offers lower capital equip-

ment costs (based on aqueous precursors), energy efficiency, and flexibility in the choice of substrates with respect to topography and thermal stability with large surface area. The obtained films are particularly stable compared with films prepared by the other non-vacuum techniques. This method is also used to incorporate dopants in thin films as precisely as possible.

The LPD process utilizes ligand-exchange hydrolysis of metal fluorocomplex species, MF_x^{(x-2n)-} and F⁻ consumptive reaction. In aqueous solution, MF_x^{(x-2n)-} is hydrolysed with water following ligand-exchange equilibrium reaction:



This reaction can be shifted to the right-hand side by adding boric acid or aluminum metal, which reacts with F⁻ ions to form more stable complex ions:



The addition of the boric acid or aluminum metal leads to the consumption of F⁻ ions and accelerates the ligand-exchange reaction. Thus, thin films are slowly deposited homogeneously on the substrates. So far, we have already developed and reported the preparation of various kinds of metal oxide

* Corresponding author. Tel.: +81-78-803-6160; fax: +81-78-803-6160.
E-mail address: deki@kobe-u.ac.jp (S. Deki).

thin films such as titanium oxide [6], vanadium oxide [7], iron oxide [8], gradient-type $\text{Si}_{1-x}\text{Ti}_x\text{O}_2$ [9], and so on [10] by the LPD method.

In this paper, we describe the fabrication and characterization of hetero-structured oxide such as Au and Pt nanoparticles-dispersed Nb_2O_5 or SiO_2 composite films by the LPD method. The characteristics of the deposited films are discussed on the basis of results obtained from X-ray diffraction (XRD), high-resolution transmission electron microscopy (HRTEM), X-ray photoelectron spectroscopy (XPS) and Fourier transform infrared spectroscopy (FT-IR).

2. Results and discussion

The deposited films are transparent, of uniform thickness and appearance, and adhere strongly to the substrates. The color of composite films has changed according to those of the heat treatment temperature. In the Au/ Nb_2O_5 system, the as-deposited film (before heat treatment) has a pale yellow, and gradually changed to deep yellow at 100 °C, a white blue at 200 °C, deep blue color at 300 °C and above, respectively. For the Au/ SiO_2 system, the composite film changed light yellow to ruby red color after treatment at 300 °C. In the case of Pt/ Nb_2O_5 system, the composite film slightly changed a pale yellow to brown color with increasing treatment up to 600 °C. These color changes are indicative of the formation of Au and Pt particles in the composite films. The thicknesses after treatment at 500 °C are about 100 nm for Au/ SiO_2 , 80 nm for Pt/ Nb_2O_5 , and 150 nm for Au/ Nb_2O_5 composite films, respectively.

2.1. Au nanoparticles dispersed- Nb_2O_5 composite film

FT-IR spectra of the Au/ Nb_2O_5 composite films with various heat treatment temperatures are shown in Fig. 1 by emphasizing the regions of changes with arrows. All deposited films show the main bands at 650–1000 cm^{-1} which are attributed to Nb–O stretching, Nb–O–Nb bridging and $\text{Nb}_3\text{–O}$ stretching modes. The bands at 1400 and 1540 cm^{-1} , and a broad one at 2800–3700 cm^{-1} are assigned to the O–H and N–H vibrations for water molecules and NH_4^+ ions, respectively [11]. Since the LPD process is performed in an aqueous solution system, water molecules can be readily absorbed and adsorbed by the film. NH_4^+ ions which are contained in the niobium source solution are enclosed in the deposited oxide film during the reaction. These O–H and N–H vibration bands completely disappear after treatment above 200 °C.

The Au 4f, Nb 3d, O 1s, F 1s, and N 1s core-level spectra for the deposited films with various heat treatment temperatures are shown in Fig. 2. These spectra are recorded at room temperature. For the Au 4f electron spectra show the typical doublet structure (Au 4f_{5/2} and Au 4f_{7/2}) due to spin–orbit splitting. From the curve-fitting result of the as-deposited

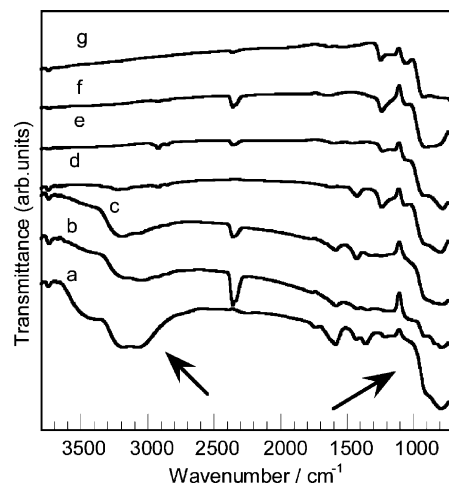
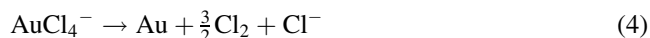


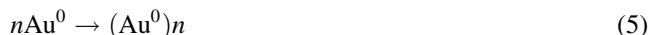
Fig. 1. FT-IR spectra of the Au/ Nb_2O_5 composite films heat-treated at various temperatures: (a) as-deposited film, and (b–g) films heat-treated at 100–600 °C, respectively.

film, the Au 4f_{7/2} peak positioned at 86.9 eV assigning to Au(III) ionic state [12]. After heating at 100 °C, this peak shifted to lower energy side as compared to that of as-deposited film indicating Au(I) ionic state. The fitting of Au 4f exhibit two binding energies for Au 4f_{7/2} at 86.9 and 86.0 eV representing Au(III) and Au(I) ionic states, respectively. For the films treated at 200 °C, the spectra become sharpened and the Au 4f_{7/2} peaks are observed near 84.0 eV assigning to metallic Au (Au^0).

The reduction Au ionic species may not occur without the decomposition of AuCl_4^- ionic species. Therefore, it is considered that AuCl_4^- ionic species are decomposed between 100 and 200 in the airflow as follows:



Au atoms produced by the decomposition of AuCl_4^- should tend to aggregate to form nanocrystal.



In the case of Nb 3d peaks, for the as-deposited film, a pair of peaks due to Nb 3d_{3/2} and Nb 3d_{5/2} core-level is observed at the binding energies of ca. 211.3 and 208.5 eV. The Nb 3d_{5/2} peak position states a higher energy than that of the bulk Nb_2O_5 (207.8 eV). The electron spectra of F 1s and N 1s are also observed at ca. 685.0 and 401.0 eV, respectively. The O 1s electron spectra show broad and asymmetrical profiles which may be connected with the presence of hydroxyl groups and adsorbed water molecule [13]. However, these peaks become sharp with increasing heat treatment temperature. It indicates the elimination of water from the film due to the treatment. The corresponding O 1s peaks of all the deposited films are centered on 530.5 eV and can be assigned to the O^{2-} constituent of the Nb_2O_5 .

The LPD process performs typical aqueous solution system, and it may be contained water molecule in the deposited film. Moreover, a small trace of ammonia ions

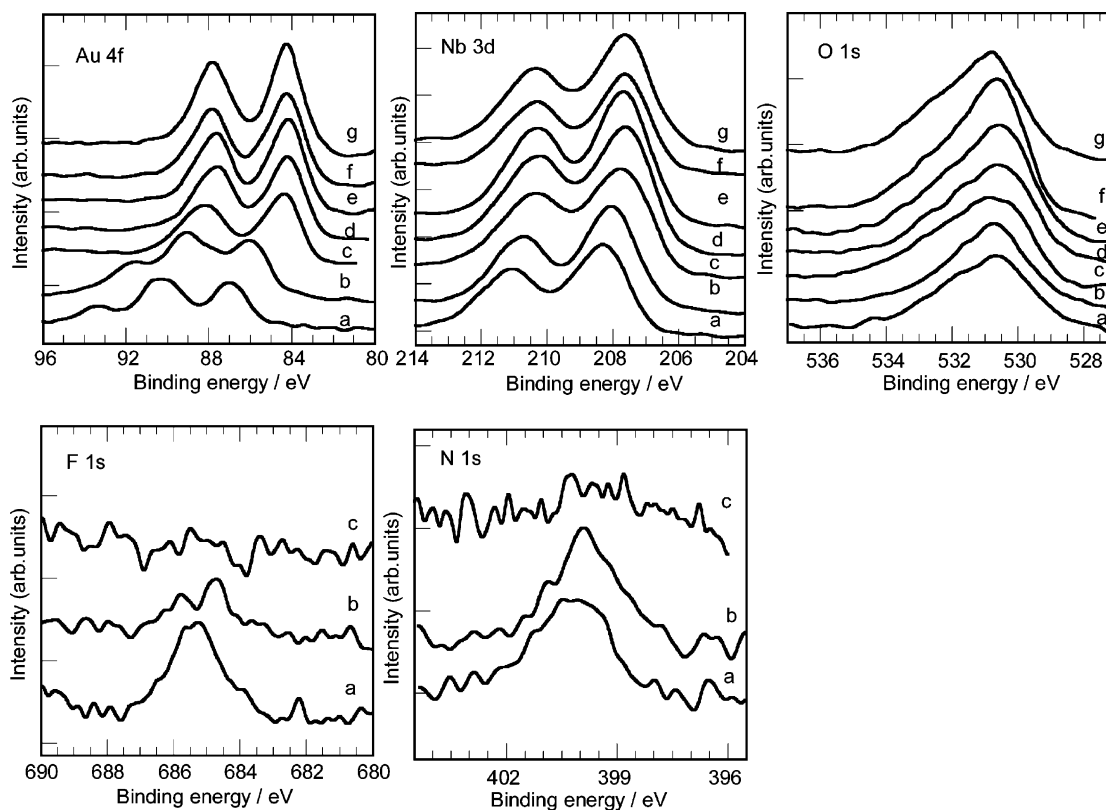


Fig. 2. Evolution of the Au 4f, Nb 3d, O 1s, F 1s, and N 1s electron spectra of the Au/Nb₂O₅ composite films heat-treated at various temperatures: (a) as-deposited film, and (b–g) films heat-treated at 100–600 °C, respectively.

may also be existed in the deposited film because of using the source material (Nb₂O₅ dissolved NH₄F·HF aqueous solution) for the thin film formation process. From the changes of Nb 3d, O 1s, F 1s, and N 1s spectra with heat treatment temperature, it can be considered that interactions such as Nb–F, Nb–OH, and Nb–OF exist in the as-deposited film. The disappearance of F 1s, N 1s peaks, and sharpening of O 1s peak with the increase of heating are indicated that the elimination of fluorine, nitrogen and water from the deposited film. Further gradually increase up to 600 °C, the Nb 3d_{5/2} and O 1s peaks were ca. 207.7 and 530.2 eV, respectively, corresponding to that of bulk Nb₂O₅. These energies are in good agreement with the other study [14].

2.2. Au nanoparticles dispersed-SiO₂ composite film

The deposited Au/SiO₂ composite films are constructed of small particles and very homogeneous, showing no crack and exfoliation. The small particles become large by heat treatment. From the FT-IR measurement, Si–O stretching (1090 cm⁻¹), Si–O bending (810 cm⁻¹) modes are observed [15]. We can confirm these absorption peaks for all composite films before and after heat treatment. XPS profile indicates that Au(III) ionic species are deposited in the as-deposited film. Au ionic species in the composite film are completely reduced to metallic Au (Au⁰) by the treatment above 200 °C. Therefore, the reduction mechanism for

Au ionic species can be considered the same as Au/Nb₂O₅ composite film system.

2.3. Micro-structure of Au/Nb₂O₅ and Au/SiO₂ composite films

Fig. 3 shows a comparison of the X-ray diffraction pattern of the Au/Nb₂O₅ and Au/SiO₂ composite films with before and after heat treatment at 500 °C. There is no distinct diffraction peak, which indicates that Nb and Si oxides have amorphous structure (Fig. 3a and b). As considered from the Scherrer's equation, the broader the peak becomes, the smaller the crystal grows. For the composite films treated at 500 °C, the two sharp diffraction peaks at ca. $2\theta = 38.1$ and 44.4° attributed to (1 1 1) and (2 0 0) reflections of Au with an fcc structure are observed (shown with white circles in the figure). These two diffraction peaks become much sharper in the pattern of Au/SiO₂ film while in those of Au/Nb₂O₅ composite film remains broad. The crystallite sizes calculated by Scherrer's equation for the diffraction line from Au(1 1 1) and the mean sizes of dispersed Au particles are estimated by plan-view TEM observation are summarized in Table 1. Gold particles grow into large aggregates in the heat-treated Au/SiO₂ composites [16]. However, in the Au/Nb₂O₅ composite film, even after treated at high temperature, the Au crystallite size remains very small. Moreover, at 500 °C, the new diffraction peaks appear at ca.

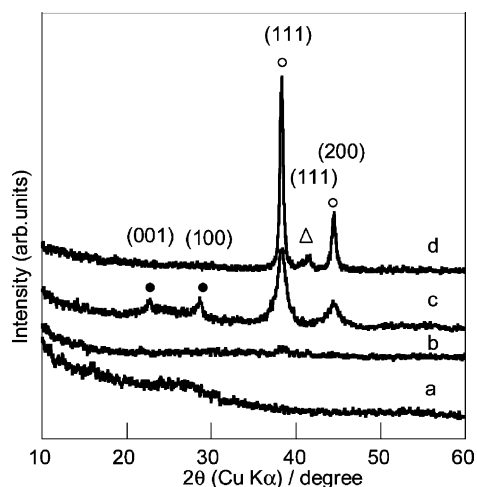


Fig. 3. XRD patterns of the deposited films: as-deposited Au/Nb₂O₅ (a), that of Au/SiO₂ (b), film heat-treated at 500 °C Au/Nb₂O₅ (c), and that of Au/SiO₂ composite films (d), respectively. (○) Au; (●) Nb₂O₅, (△) Si (substrate).

$2\theta = 22.6$ and 28.6° due to the hexagonal TT-Nb₂O₅ phase (shown with black circles in the Fig. 3c) (JCPDS 28-317 data.). The TT phases are named by German workers and signified the low- (tief) and very low-temperature (tief-tief) forms of Nb₂O₅ [17].

The cross-sectional HRTEM observation of heat-treated Au/Nb₂O₅ (600 °C, 1 h) and Au/SiO₂ (300 °C, 1 h) composite films are shown in Fig. 4. It can be clearly observed that the dark patches, Au particles are homogeneously dispersed into the Nb₂O₅ and SiO₂ matrices. Au nanoparticles are uniformly situated not only on the surface but also inside of the composite film. Lattice fringe corresponding to Nb₂O₅(0 0 1) plane are observed with the spacing of 0.41 nm and the Nb₂O₅ nanocrystalline particles (ca. 10 nm) are situated all over the composite film. It can be clarified that not only Au ionic species are reduced to Au metal particles but also Nb₂O₅ matrix is crystallized by the heat treatment.

2.4. Optical properties of Au/Nb₂O₅ and Au/SiO₂ composite films

Fig. 5 shows the optical absorption spectra of the Au/Nb₂O₅ and Au/SiO₂ composite films with before and after

Table 1
Crystallite and mean particle sizes of the dispersed Au metal particles in the composite films heat-treated at various temperatures

	Heat-treatment temperature (°C)	Crystallite size (nm)	Mean particle size (nm)
Au/Nb ₂ O ₅	300	8.0	7.0
Au/SiO ₂	300	11.0	10.5
Au/Nb ₂ O ₅	500	10.0	9.5
Au/SiO ₂	500	16.5	16.0

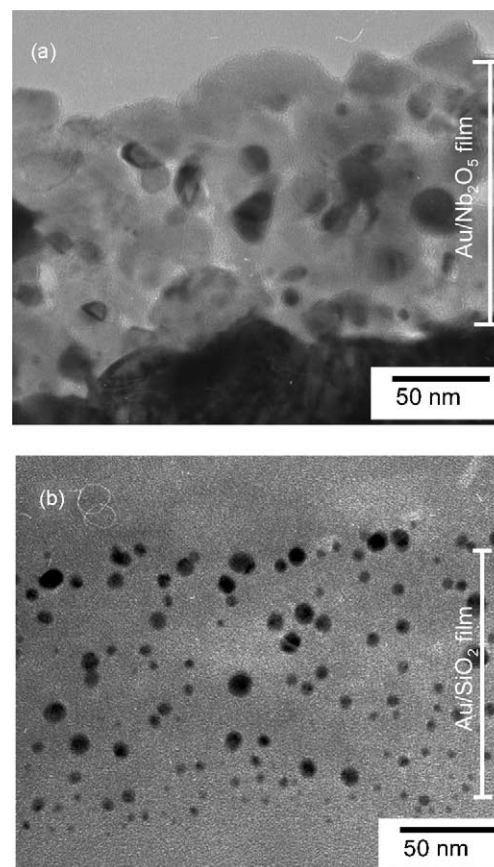


Fig. 4. Cross-sectional HRTEM images of the deposited composite films: (a) Au/Nb₂O₅ (600 °C, 1 h), and (b) Au/SiO₂ (300 °C, 1 h), respectively.

heat treatment at 500 °C. In both cases of as-deposited films, the surface plasmon resonance (SPR) peaks of Au particles are not discernible. In the heat-treated samples, the SPR peaks of Au particles are observed at 550 and 580 nm for Au/SiO₂ and Au/Nb₂O₅ composite films, respectively. The

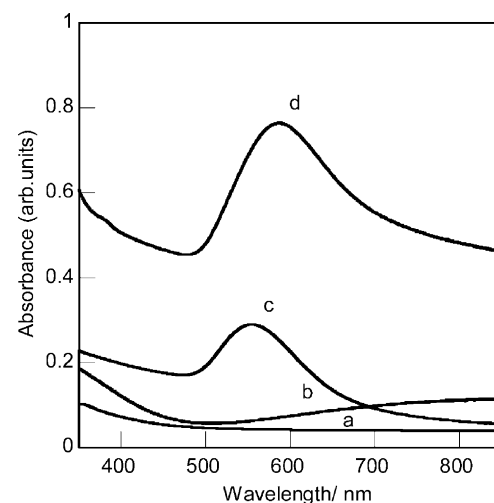


Fig. 5. Optical absorption spectra of the deposited films: as-deposited Au/SiO₂ (a), that of Au/Nb₂O₅ (b), and film heat-treated at 500 °C Au/Nb₂O₅ (c), and that of Au/SiO₂ composite films (d), respectively.

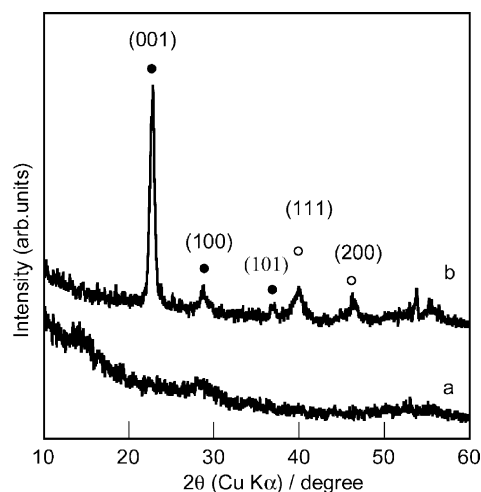


Fig. 6. XRD patterns of the Pt/Nb₂O₅ composite films: (a) as-deposited film, and (b) film heat-treated at 600 °C, respectively. (○) Pt; (●) Nb₂O₅.

surface plasmon resonance of Au nanoparticles is greatly affected by the surrounding metal oxides. We assume that strong interactions exist between oxide and gold, which causes the oxide to surround gold nanoparticles and keep them from aggregating. It is reported that small particles are known to interact well with transition metal oxides and very weak interaction with non-transition metal oxides [18,19]. In this study, gold nanoparticles are also found to interact with SiO₂, a non-transition metal oxide, although the interaction is smaller than that with Nb₂O₅, because Au nanoparticles remain smaller in Nb₂O₅ than in SiO₂.

The plasmon band is affected by the volume fraction and micro-structures of the embedded metal clusters, together with the dielectric constant of the matrix. These are key factors to control the optical properties of metal nanoparticles [20,21]. In our study, the red shift of SPR peaks is observed in the Au/SiO₂ and Au/Nb₂O₅ composite films causing particle size effect with increasing treatment temperature.

2.5. Pt nanoparticles dispersed-Nb₂O₅ composite film

X-ray diffraction patterns of the Pt/Nb₂O₅ composite films, as-deposited and heat-treated at 600 °C are shown in Fig. 6. The deposited films exhibit amorphous nature, i.e. no discernible diffraction peaks are observed up to 500 °C. After at 600 °C, the diffraction peaks (indicating the crystallinity) appear approximately at $2\theta = 22.6$, 28.6 and 36.8° (shown with black circles in the figure) assigned to the hexagonal TT-Nb₂O₅ phase (JCPDS 28-317 data). Furthermore, the two sharp diffraction peaks are observed approximately at $2\theta = 39.8$ and 46.4° (shown by white circles in the figure) attributed to (1 1 1) and (2 0 0) reflection lines of the cubic structure of Pt, respectively.

XPS are measured for Pt 4f electron band of the composite films as a function of heat treatment temperatures. For the

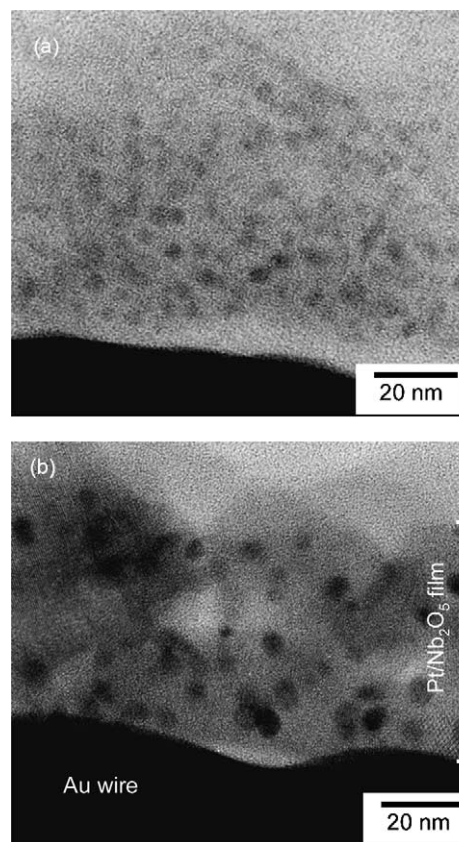


Fig. 7. Cross-sectional HRTEM images of the Pt/Nb₂O₅ composite films deposited on gold wire: (a) as-deposited film, and (b) film heat-treated at 300 °C, respectively.

as-deposited film, the Pt 4f_{7/2} peak is observed at 72.6 eV and assigned to Pt(II) ionic state. This indicates that the Pt is situated in the niobium oxide matrix as ionic state in the as-deposited film. The peak position of Pt 4f_{7/2} shifts to the lower energy side with increasing temperatures. At 300 °C, Pt 4f peak separates into two binding energies for Pt 4f_{7/2} peaks at 72.6 and 71.2 eV standing for Pt(II) ionic state and metallic Pt (Pt⁰) state, respectively [22]. For the films treated at 500 °C, the Pt 4f_{7/2} peaks are observed near 71.0 eV. Therefore, the partial reduction of Pt(II) ionic species in the deposited films is expected to be observed after being treated at 200 °C and the complete reduction may be occurred about 500 °C.

Fig. 7 shows the cross-sectional HRTEM images of the Pt/Nb₂O₅ composite films, as-deposited and heat-treated at 600 °C. The as-deposited film exhibits an amorphous nature (Fig. 7a). This result is good agreement with that of XRD result (Fig. 6a). In contrast, the spherical Pt particles are homogeneously dispersed into the Nb₂O₅ matrix after treatment at 600 °C (Fig. 7b). The size of Pt particles (with mean sizes of 2–6 nm) dispersed in the film are mostly single crystal and distributed around the Nb₂O₅ nanocrystalline particles. The Nb₂O₅ nanocrystalline particles (nearly 10 nm) are observed throughout the entire deposited film. These results signify that the heat treatment not only causes

the reduction of Pt(II) ionic species to Pt particles but also involves the crystallization of Nb₂O₅ matrix.

3. Experimental

3.1. Preparation of Au and Pt nanoparticles dispersed-Nb₂O₅ and SiO₂ composite films

As the niobium source solution for deposition of Nb₂O₅ film, niobium(V) oxide (Nb₂O₅; Taki Chemical Co. Ltd.) powder and NH₄F·HF (Nacalai Tesque Inc.) aqueous solution were used. This solution was obtained by dissolving Nb₂O₅ powder (7.4 g, 20 mmol) in NH₄F·HF (57.9 g, 1.0 mol) aqueous solution (1000 ml). For deposition of SiO₂ film, ammonium silicohexafluoride acid ((NH₄)₂SiF₆) was employed. The boric acid (H₃BO₃) was used as a F⁻ scavenger. As platinum and gold precursors, Tetra-ammineplatinum chloride (Pt(NH₃)₄Cl₂) and tetra-chloroauric (HAuCl₄·4H₂O) acid solutions were prepared.

Various substrates were employed depending on the needs of the different characterization techniques. The non-alkali glass (corning 7059) and Si(1 1 1) wafers were used as substrates for the XPS, FT-IR and XRD measurements. For the HRTEM cross-sectional observation, the composite films were deposited on gold wire. After being degreased and washed ultrasonically, the substrates were vertically placed in a freshly prepared solution containing 4.0 mM (1 M = mol dm⁻³) niobium source solution, 0.2 M H₃BO₃, 0.4 mM HAuCl₄·4H₂O for Au/Nb₂O₅ composite film and 0.6 mM Pt(NH₃)₄Cl₂ for Pt/Nb₂O₅ composite film, were kept 30 °C for 40 h. They were then removed and washed with deionized water. After that the samples were dried in ambient temperature. The deposited films were pre-treated at 100–600 °C in airflow for 1 h before being removed for spectroscopic and microscopic observations. For the preparation of Au/SiO₂ composite films, 0.1 M (NH₄)₂SiF₆, 0.2 M H₃BO₃, and 0.4 mM HAuCl₄·4H₂O were used with the same manner under 40 °C for 48 h.

3.2. Characterization of the deposited composite films

The phases and the crystallographic structures of the deposited films were determined by XRD measurement on Rigaku RINT-2100 diffractometer equipped with a thin film attachment using Cu K α radiation. The incident angle of the X-ray to the sample was 1°. XPS analyses were carried out in a KRATOS, XSAM 800 with Mg K α radiation (1253.6 eV) for the determination of the oxidation state and the chemical structure of materials. The C 1s peak (284.6 eV) was used as reference for the correction of the XPS positions of the obtained films. TEM images, which were obtained using a JEOL JEM-2010 at acceleration voltage of 200 kV, were used to observe the morphology and size of particles in the composite films. The preparation of the cross-sectional HRTEM observation is expressed

detail in the [10]. The infrared spectra of the films were recorded with a FT/IR615 (JASCO) spectrometer equipped with a RAS attachment (PR-510, JASCO) in the range of 650–3650 cm⁻¹. The resolution and incident angle were 2 cm⁻¹ and 65°, respectively.

4. Conclusions

We have developed a very simple soft solution process for fabrication of hetero-structured oxide thin films from metal fluorocomplex aqueous solution such as Au and Pt nanoparticles-dispersed metal oxide (M = Nb or Si) thin films. The Nb₂O₅ thin films containing Pt, Au ionic species are deposited from a mixed solution of niobium source, H₃BO₃, Pt(NH₃)₄Cl₂ and HAuCl₄ aqueous solutions under the ambient temperature and atmosphere. For Au/SiO₂ composite film, (NH₄)₂SiF₆ solution is used as a mother solution. The Pt(II) and Au(III) ionic species are deposited in Nb₂O₅ and SiO₂ matrices. They are reduced to their metallic state after treatment above 200 °C. All deposited films are X-ray amorphous up to treatment of 500 °C, above of which the hexagonal structure of TT-Nb₂O₅ are observed although silica is still amorphous. The dispersion of particles in the matrices is homogeneous. The size of dispersed particles can be controlled by heat treatment temperature. It is also clear that, gold nanoparticles are also found to interact with SiO₂, although the interaction is smaller than that with Nb₂O₅ showing the size of Au nanoparticles remain smaller in Nb₂O₅ than in SiO₂. The LPD method enables us to form nanoscale structure in solid dielectric materials, in which the fine structures such as size and concentration of dispersed metal particles.

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